	Application No.	Applicant(s)
Notice of Allowability	10/023,665	HIROKI ET AL.
	Examiner	Art Unit
	Roberts Culbert	1763
The MAILING DATE of this communication appear All claims being allowable, PROSECUTION ON THE MERITS IS (herewith (or previously mailed), a Notice of Allowance (PTOL-85) of NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT RIGORY of the Office or upon petition by the applicant. See 37 CFR 1.313 1. This communication is responsive to the amendment filed 6 2. The allowed claim(s) is/are 1.2.4-6 and 8. 3. The drawings filed on 21 December 2001 are accepted by the Acknowledgment is made of a claim for foreign priority under a) All b) Some* c) None of the: 1. Certified copies of the priority documents have 2. Certified copies of the priority documents have 3. Copies of the certified copies of the priority documents have	OR REMAINS) CLOSED in this apport of the appropriate communication GHTS. This application is subject to and MPEP 1308. 6/2/04. the Examiner. der 35 U.S.C. § 119(a)-(d) or (f). been received. been received in Application No	plication. If not included a will be mailed in due course. THIS o withdrawal from issue at the initiative or withdrawal from its analysis.
International Bureau (PCT Rule 17.2(a)). * Certified copies not received: Applicant has THREE MONTHS FROM THE "MAILING DATE" of	of this communication to file a reply	
noted below. Failure to timely comply will result in ABANDONMETHIS THREE-MONTH PERIOD IS NOT EXTENDABLE. 5. A SUBSTITUTE OATH OR DECLARATION must be submit INFORMAL PATENT APPLICATION (PTO-152) which gives	ted. Note the attached EXAMINER	'S AMENDMENT or NOTICE OF tion is deficient.
 CORRECTED DRAWINGS (as "replacement sheets") must (a) including changes required by the Notice of Draftspersor 1) hereto or 2) to Paper No./Mail Date (b) including changes required by the attached Examiner's Paper No./Mail Date Identifying indicia such as the application number (see 37 CFR 1.8 each sheet. Replacement sheet(s) should be labeled as such in the 7. DEPOSIT OF and/or INFORMATION about the depos attached Examiner's comment regarding REQUIREMENT F 	on's Patent Drawing Review (PTO- Amendment / Comment or in the O 34(c)) should be written on the drawing the header according to 37 CFR 1.121(c) it of BIOLOGICAL MATERIAL n	office action of ngs in the front (not the back) of d). nust be submitted. Note the
Attachment(s) 1. Notice of References Cited (PTO-892) 2. Notice of Draftperson's Patent Drawing Review (PTO-948) 3. Information Disclosure Statements (PTO-1449 or PTO/SB/08 Paper No./Mail Date 4. Examiner's Comment Regarding Requirement for Deposit of Biological Material	6. ☐ Interview Summary Paper No./Mail Date 7. ☐ Examiner's Amendm	e

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EXAMINER'S AMENDMENT

An examiner's amendment to the record appears below. Should the changes and/or additions be unacceptable to applicant, an amendment may be filed as provided by 37 CFR 1.312. To ensure consideration of such an amendment, it MUST be submitted no later than the payment of the issue fee.

Authorization for this examiner's amendment was given in a telephone interview with Douglas Pinsky on 7/16/04.

The application has been amended as follows:

Amend Claim 4(renumbered as Claim 3) to depend on Claim 1.

Amend Claim 8(renumbered as Claim 6) to depend on Claim 5(renumbered as Claim 4).

Continued Examination Under 37 CFR 1.114

A request for continued examination under 37 CFR 1.114, including the fee set forth in 37 CFR 1.17(e), was filed in this application after final rejection. Since this application is eligible for continued examination under 37 CFR 1.114, and the fee set forth in 37 CFR 1.17(e) has been timely paid, the finality of the previous Office action has been withdrawn pursuant to 37 CFR 1.114. Applicant's submission filed on 6/2/04 has been entered.

Allowable Subject Matter

Claims 1, 2, 4-6, and 8 are allowed.

The following is an examiner's statement of reasons for allowance:

The prior art of record fails to teach or render obvious a method for manufacturing a liquid ejecting head, in which liquid flow paths are defined by combining an element substrate having a plurality of discharge energy generating elements for applying discharge energy to liquid with a nozzle member having a plurality of liquid discharge nozzle grooves and an opening communicating with said nozzle grooves, comprising the steps of: preparing at least one material common to said element substrate having a first surface of <110> crystal face orientation as a base material of said nozzle member; forming etching mask layers on said first surface of the base material of said nozzle member for forming said

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mask layer on said first surface of the base material; forming a recessed portion corresponding to said opening in said second surface of the base material by patterning said mask layer on said second surface of the base material by patterning said mask layer on said second surface of the base material and by effecting etching in said second surface via said mask layer of said second surface; and after forming said recessed portion, forming said nozzle grooves and said opening in the base material for communicating said recessed portion with said nozzle grooves, by patterning said mask layer on said first surface of the base material and by effecting etching in said first surface and said recessed portion via said mask layer of said first surface and said mask layer of said second surface.

Similarly, the prior art of record fails to teach or render obvious a method for manufacturing a liquid ejecting head in which liquid flow paths are defined by combining an element substrate having a plurality of discharge energy generating elements for applying discharge energy to liquid with a nozzle member having a plurality of liquid discharge nozzle grooves and a liquid chamber communicating with said nozzle grooves and an opening communicating with said liquid chamber, comprising the steps of: preparing at least one material common to said element substrate having a first surface of <110> crystal face orientation as a base material of said nozzle member; forming etching mask layers on said first surface of the base material of said nozzle member for forming said nozzle grooves and said liquid chamber and on a second surface opposite to said first surface, respectively; before patterning said mask laver on said first surface of the base material; forming a recessed portion corresponding to said opening in said second surface of the base material by patterning said mask layer on said second surface of the base material and by effecting etching in said second surface via said mask layer of said second surface; and after forming said recessed portion, forming said nozzle grooves, said liquid chamber, and said opening in the base material for communicating said recessed portion with said liquid chamber, by patterning said mask layer on said first surface of the base material and by effecting etching in said first surface and said recessed portion via said mask layer of said first surface and said mask layer of said second surface.

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Any comments considered necessary by applicant must be submitted no later than the payment

of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such

submissions should be clearly labeled "Comments on Statement of Reasons for Allowance."

Conclusion

Any inquiry concerning this communication or earlier communications from the examiner should

be directed to Roberts Culbert whose telephone number is (571) 272-1433. The examiner can normally

be reached on Monday-Friday (7:30-4:00).

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor,

Gregory Mills can be reached on (571) 272-1439. The fax phone number for the organization where this

application or proceeding is assigned is 703-872-9306.

Information regarding the status of an application may be obtained from the Patent Application

Information Retrieval (PAIR) system. Status information for published applications may be obtained from

either Private PAIR or Public PAIR. Status information for unpublished applications is available through

Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should

you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC)

at 866-217-9197 (toll-free).

R. Culbert

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